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(54) Title (EN): NEGATIVE HEEL SHOE HAVING SPECIAL SOLE PATTERN

(54) Title (FR): CHAUSSURE À TALON SURBAISSÉ AYANT UN MOTIF DE SEMELLE SPÉCIAL

(54) Title (ZH): 有特殊鞋底花纹的负跟鞋

(57) Abstract:

(EN): A negative heel shoe having a special sole pattern is provided, and is characterized in that a rear end (1) portion of the outsole has a tooth-shaped pattern that is inclined forward. By means of the shoe, specific problems caused by negative heel techniques are alleviated, and possible risk of accidents during the adaptation period is reduced. The shoe is good for preventing the heel from sliding forward, and facilitates mental ease and posture adjustment. The absolute thickness of the shoe heel is also relatively reduced. In this way, proprioception of the human body is maintained to the utmost, and gaits more conforming to healthy gaits in normal walking and closer to natural gaits are facilitated.

(FR): L'invention concerne une chaussure à talon surbaissé ayant un motif de semelle spécial, et caractérisée en ce qu'une partie d'extrémité arrière (1) de la semelle d'usure a un motif en forme de dents qui est incliné vers l'avant. Au moyen de la chaussure, des problèmes spécifiques provoqués par des techniques à talon surbaissé sont atténués, et l'éventuel risque d'accidents pendant la période d'adaptation est réduit. La chaussure est bonne pour empêcher le talon de glisser vers l'avant, et facilite tout ajustement en termes de posture et d'aptitude mentale. L'épaisseur absolue du talon de chaussure est également relativement réduite. De cette manière, la proprioception du corps humain est maintenue au maximum, et les démarches se conformant plus aux démarches saines au cours de la marche normale et plus proches des démarches naturelles sont facilitées.

(ZH): 一种有特殊鞋底花纹负跟鞋,其特征是:鞋底后端(1)部位的外底有向前倾斜的齿状花纹。弥补负跟技术带来的特定问题,减小了在适应期内可能产生的意外风险,有利于防止足跟部位的向前滑动,有利于精神的放松,有助于姿势的调整,又相对减小了鞋跟的绝对厚度,最大程度的保护了人体的本体感觉,更顺应正常行走的健康步态,更接近自然步态。

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